

Tailoring the optical properties of silica irradiated with swift heavy ions

A. Rivera,¹ A. Prada,¹ O. Peña-Rodríguez,¹
 J. Manzano-Santamaria,^{2,3} M. Crespillo,³
 J. Olivares^{3,4} and F. Agulló-López³

¹Instituto de Fusión Nuclear, Universidad Politécnica de Madrid
²Euratom/CIEMAT Fusion Association
³Centro de Micro-Análisis de Materiales, Universidad Autónoma de Madrid
⁴Instituto de Óptica, Consejo Superior de Investigaciones Científicas

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CSIC CMAM

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Outline

- Introduction
- Molecular dynamics
 - Electronic excitation
- Linking simulations with experiments
 - Optical measurements
- Conclusions

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Amorphous silica

- Swift ion irradiation
 - Electronic sputtering
 - Density variation
 - Defect production
- Relevant effects in nuclear fusion, optics and other fields

Amorphous silica

Refractive index change

Waveguides

Manzano *et al.*, Nucl. Instrum. Meth. B 268 (2010) 3147

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INDUSTRIALES ETSI | UPM Electronic excitation

- Not well understood
- Permanent damage
- Modification of properties
- Defect annealing
- Nano-track formation
- Complex energy transfer mechanisms
- Goal: thermal effects by MD

Schiwietz *et al.*, Nucl. Instrum. Meth. B 226 (2004) 683

INDUSTRIALES ETSI | UPM Molecular dynamics

- Super con
- Typical 51
- Code MD
- Feuston &
- Simulation
- Simulation
- PBC in thr

INDUSTRIALES ETSI | UPM Molecular dynamics

- Can't explain ion-solid energy transfer
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Waligórski, Szenes *et al.*, Nucl. Instrum. Meth. B 166-167 (2000) 903

INDUSTRIALES ETSI | UPM MD results (30 keV/nm)

- Ion irradiation strongly affects the material:
 - Density change
 - Refractive index
 - Defects
 - Network structure
 - Electronic sputtering (surface)

INDUSTRIALES ETSI | UPM Density change

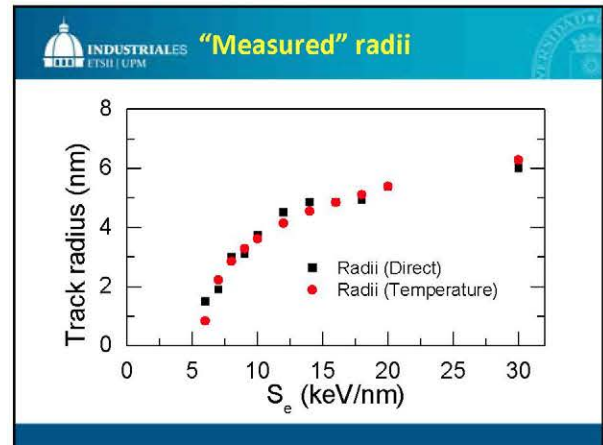
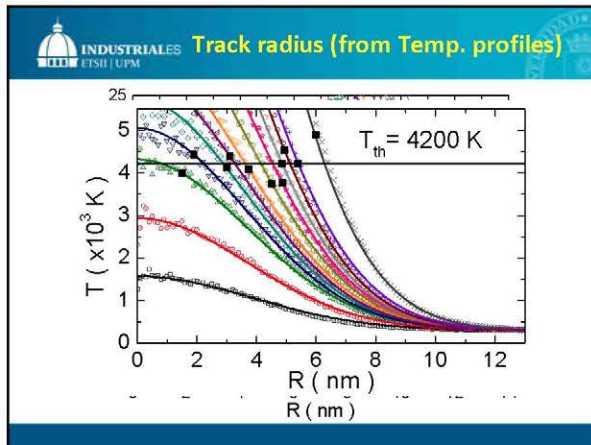
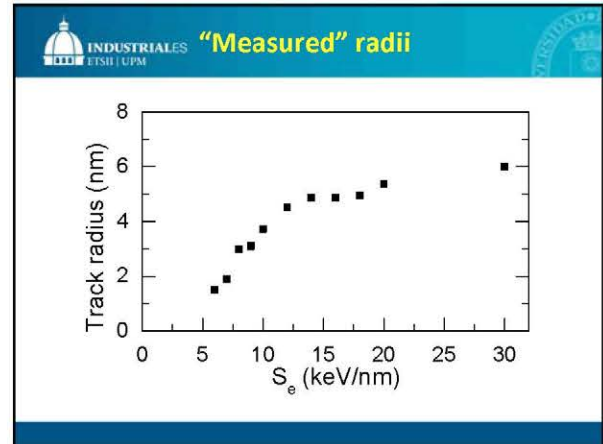
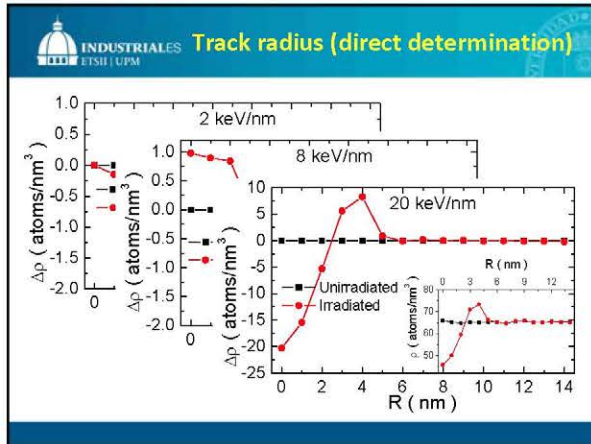
Energy loss [keV/nm]	Track radius R [nm]	Atomic density [atoms/nm ³]
2	0	65
2	2	65
2	4	65
2	6	65
2	8	65
2	10	65
2	12	65
2	14	65
6	0	65
6	2	65
6	4	65
6	6	65
6	8	65
6	10	65
6	12	65
6	14	65
10	0	65
10	2	65
10	4	65
10	6	65
10	8	65
10	10	65
10	12	65
10	14	65
14	0	65
14	2	65
14	4	65
14	6	65
14	8	65
14	10	65
14	12	65
14	14	65
20	0	65
20	2	65
20	4	65
20	6	65
20	8	65
20	10	65
20	12	65
20	14	65
30	0	65
30	2	65
30	4	65
30	6	65
30	8	65
30	10	65
30	12	65
30	14	65

INDUSTRIALES ETSI | UPM Density change

Energy loss [keV/nm]	Total track radius R [Å]
4	25
6	30
8	42
10	48
12	52
14	55
16	58
18	60

- Previous experimental and MD work show similar effects

Kluth *et al.*, Phys. Rev. Lett. 101 (2008) 175503



- INDUSTRIALES** ETSI | UPM **In summary**
- Tree clearly-defined regions
 - Below threshold ($\sim 4-6$ keV/nm) there are no tracks
 - For low S_e (< 12 keV/nm) we observed compact cylindrical tracks
 - For high S_e (> 12 keV/nm) we obtained a core-shell track. The core region has a lower density whereas for the shell the opposite is true

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 - **Linking simulations with experiments**
 - Optical measurements
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Linking simulations with experiments

- Comparing the simulations with experimental results is very desirable but it is not an easy task
- Microscopic measurements
 - Directly comparable
 - Hard to perform
- Macroscopic measurements
 - Easier to obtain
 - Comparison with simulations not always obvious

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Optical measurements

- "Macroscopic" measurement
- Very fast (we could follow the kinetics at one-second intervals)
- Easy to do
- Easy to analyze
- Direct conversion from track density/stoichiometry to refractive index are possible
- Effective medium approximations (EMA) provide an straightforward mean to represent the refractive index kinetics

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In situ reflectance

CMAM

Ion beam $\approx 6 \times 6 \text{ mm}^2$

Sample at $\approx 15^\circ$

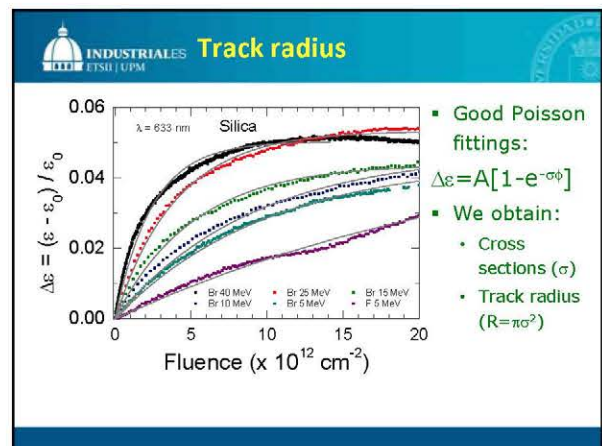
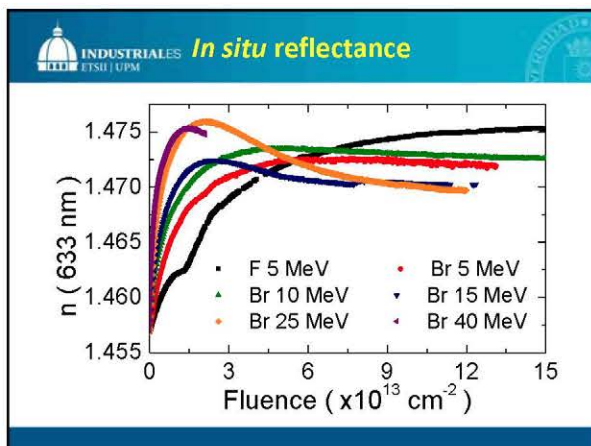
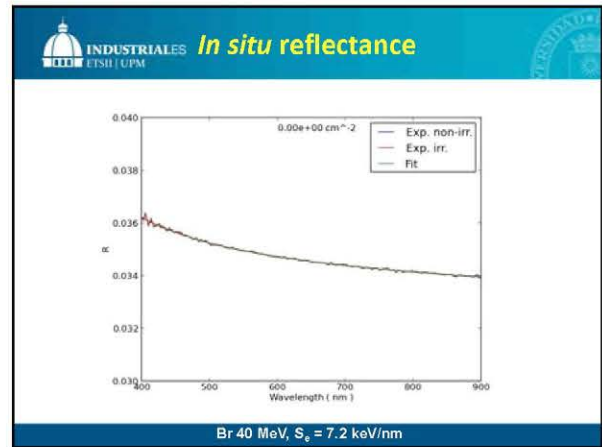
2 mirrors inside chamber

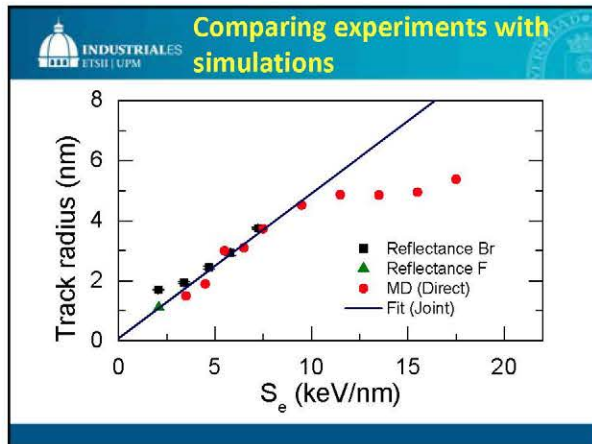
Refractive index

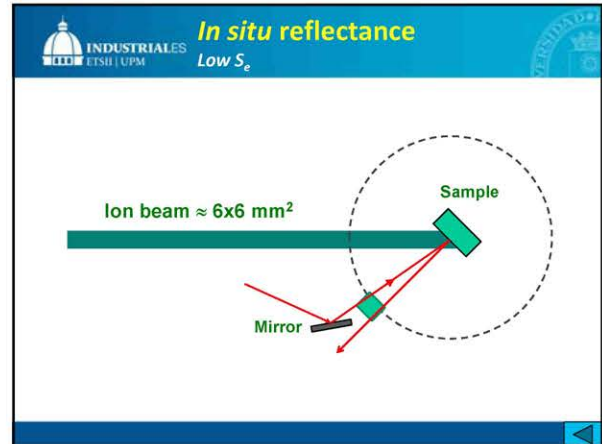
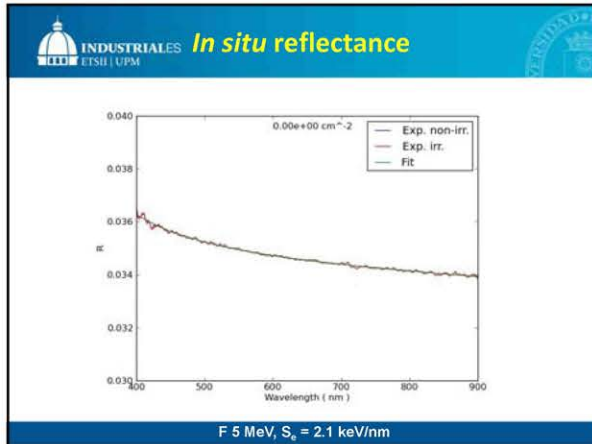
Snell's law: $n_1 \sin(\theta_i) = n_2 \sin(\theta_t)$

Fresnel coefficients: $r = r_s = r_p = \frac{n_1 - n_2}{n_1 + n_2}$

Reflectance: $R = |r|^2, T = 1 - R$







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In situ reflectance

Low S_e

Ion beam $\approx 6 \times 6$ mm²

Sample at $\approx 15^\circ$

2 mirrors inside chamber

Refractive index

Fresnel coefficients

$$n_1 \sin(\theta_1) = n_2 \sin(\theta_2) = n_3 \sin(\theta_3)$$

$$r = r_s = r_p = \frac{n_1 - n_2 + n_2^2 - n_3^2 \exp(-2i\beta)}{n_1 + n_2 + n_2 + n_3 \exp(-2i\beta)}$$

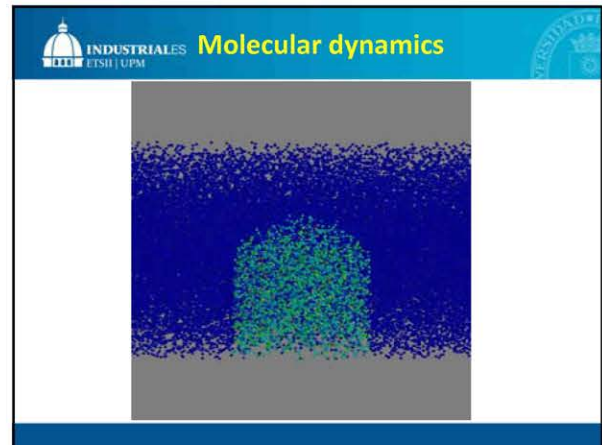
$$1 + \frac{n_1 - n_2}{n_1 + n_2} \frac{n_2 - n_3}{n_2 + n_3} \exp(-2i\beta)$$

Phase factor

Compaction

$$\beta = 2\pi \left(\frac{d}{\lambda} \right) n_2$$

$R = |r_s|^2, T = 1 - R$



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MD results (12 keV/nm)

- Ion irradiation strongly affects the material:
 - Density change
 - Refractive index
 - Defects
 - Network structure
 - Electronic sputtering (surface)

